

# Evaluation of Thermal Control Coatings and Polymeric Materials Exposed to Ground Simulated Atomic Oxygen and Vacuum Ultraviolet Radiation

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# ACRONYMS AND ABBREVIATIONS

А	amps
AO	atomic oxygen
AODTS	Atomic Oxygen Drift Tube System
°C	degrees Centigrade
CAA	chromic acid anodize
cm	centimeter
ESH	equivalent Sun hours
EUV	enhanced ultraviolet radiation
eV	electron volt
°F	degrees Fahrenheit
FEP	fluorinated ethylene propylene
GHz	gigahertz
in	inch
km/s	kilometer per second
kW	kilowatt
LDEF	Long Duration Exposure Facility
LEO	low-Earth orbit
LPSR	laboratory portable spectroreflectometer
mi	mile
mi/h	miles per hour
MSFC	Marshall Space Flight Center
nm	nanometer
PEEK	polyetheretherketone
PPPL	Princeton Plasma Physics Laboratory

RF	radio frequency
SAA	sulfuric acid anodize
UV	ultraviolet
VUV	vacuum ultraviolet
w	watts
$\mu$ m	micrometer

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#### TECHNICAL PAPER

#### EVALUATION OF THERMAL CONTROL COATINGS AND POLYMERIC MATERIALS EXPOSED TO GROUND SIMULATED ATOMIC OXYGEN AND VACUUM ULTRAVIOLET RADIATION

#### **INTRODUCTION**

Over the past decade, aerospace designers, scientists, and engineers have worked to achieve a better understanding of the space environment and its effect on potential engineering materials and material processes. Material durability data generated from retrieved long-term space satellite experiments and from short-term space shuttle flight experiments have proven to be invaluable to the material scientist community. However, the cost in terms of time and dollars for this type of testing is often prohibitive. As a result, aerospace designers must increasingly rely on data generated from ground test simulations.

The low-Earth orbit (LEO) environment is defined as that region of space between 200 and 1,000 km (124 to 621 mi) above the Earth and is characterized by the presence of atomic nitrogen, hydrogen, helium, and, most predominately, atomic oxygen (AO). Produced by the interaction of molecular oxygen and ultraviolet (UV) radiation, AO has been shown to produce considerable damage to orbiting spacecraft that typically travel in this region at a velocity on the order of 8 km/s (18,000 mi/h). At this velocity, AO impacts the surface of the space vehicle with an energy of approximately 5 to 7 eV, causing significant erosion and oxidation damage to exposed materials.

NASA's plans for the development of a space station involve placement of the spacecraft within the LEO environment. In order to evaluate environmental effects on potential space station materials, various thermal control coatings and polymeric materials were exposed to AO and vacuum ultraviolet (VUV) radiation, singly and combined, in a series of tests conducted in the Princeton Plasma Physics Laboratory (PPPL) 5 eV Neutral Atomic Oxygen Facility and in the MSFC EH15 Atomic Oxygen Drift Tube System (AODTS). Thermal control samples evaluated in this study included black duranodic anodized, chromic acid anodized, and sulfuric acid anodized aluminum, an inorganic black paint (currently under development by AZ Technology), Z93 white paint samples with the original PS7 binder and the new K2130 binder, Chemfab 250 beta cloth, with and without aluminization. Polymeric samples evaluated in this test series included bulk Halar<sup>TM</sup>, bulk polyetheretherketone (PEEK), and silverized FEP Teflon<sup>TM</sup>. Samples were evaluated for changes in mass, thickness, solar absorptance, and infrared emittance.

Oftentimes, controversies arise among investigators concerning the accuracy of measured optical/thermal properties made using different spectroreflectometers and techniques. Thus, in addition to investigating material durability, a secondary goal of this test series was to evaluate and compare measurements from two different spectroreflectometers typically used by MSFC EH15 investigators and by the private sector to measure total hemispherical reflectance/thermal solar absorptance. The EH15 Beckman DK2 spectroreflectometer was used for both the PPPL and AODTS test specimens to measure diffuse reflectance from 200 to 2,500 nm. This instrument uses a 20.3-cm (8-in) diameter integrating sphere coated with magnesium oxide in which the sample is centrally located. In addition, reflectance measurements were also made using the AZ Technology laboratory portable spectroreflectometer (LPSR). This instrument measures diffuse reflectance from 250 to 2,500 nm using a 10-cm (4-in) diameter integrating sphere. In this reflectometer, measurements are made with the sample located at the rear of the integrating sphere.

#### **TEST DESCRIPTION**

The Neutral Atomic Oxygen Beam Facility (fig. 1) located at the PPPL was developed under contract with MSFC. The system produces a 5-eV neutral AO beam by placing a metal plate in contact with magnetically (3 to 4 kgauss) confined AO plasma. The AO plasma is produced by a radio frequency (RF) driven lower hybrid plasma source. A magnetron supplies 1 kW of power at a frequency of 2.45 GHz to the center pin to produce the plasma. Because of the facility geometry, the AO plasma is magnetically confined such that a 1-cm (0.39-in) diameter plasma column is produced on centerline of the test chamber. The plasma column interacts with an electrically biased metallic plate. The bias applied to the plate accelerates ions from the plasma to the plate. During the acceleration process, the ions gain energy equal to the difference in the plasma potential and the neutralizer plate bias. Once the ions hit the plate, they collect an electron from the metal lattice and become neutral. Following collision with the neutralizer plate, the atoms are reflected toward the test specimen at a fraction of their precollision energy. The fraction of energy lost by the reflected atoms is a function of the type of material used to make the neutralizer plate. Because the energy of the reflected atom depends on the plasma potential, which is inherently subject to slight variations, not all atoms will be accelerated by the same potential difference. Thus, the reflected atoms will have a slight energy distribution.<sup>1</sup>

To best simulate orbital AO, the beam facility supplies 5-eV AO atoms, but the source is tunable from 3 to 20 eV. The limiting factor in the length of test runs in the system is the heating of the RF electrode. During operation of the system, the neutralizer plate collects nearly 4 A of ion current from the plasma. In order to maintain space charge conditions, the same amount of electron current must be lost from the plasma. Most of the electrons are collected by the electrode. Heating in the system has been limited by operating in a pulsed fashion with a duty cycle between 5 and 15 percent on-time.

The AO flux produced by the PPPL system ranges from  $5 \times 10^{15}$  to  $1 \times 10^{16}$  atoms/cm<sup>2</sup>. During production of the AO plasma, the system produces electromagnetic radiation. This radiation is produced primarily during the dissociation and ionization process. Attempts to identify and quantify the radiation

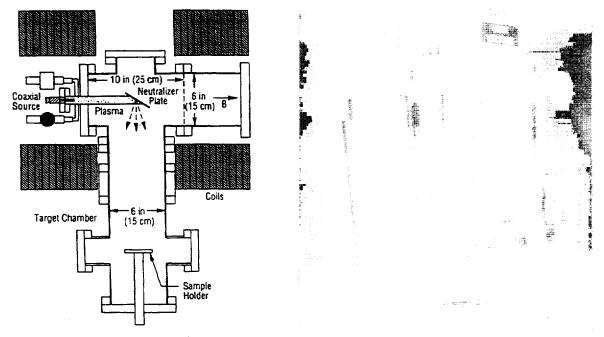


Figure 1. PPPL 5-eV AO test system.

using a photodiode with appropriate narrow band filters indicated that the primary radiation line was 130 nm, the AO resonant peak in the VUV region. The VUV intensity was determined to be nearly 200 times the Sun's intensity averaged over the duty cycle. In order to eliminate possible magnetic interactions, appropriate shielding is placed around the diode.

The PPPL facility was used to expose various 2.54-cm (1-in) diameter samples over a series of two separate runs in the facility. Test samples were placed in specially designed sample fixtures capable of holding 14 individual specimens. These specimens were placed in the test chamber 5.5 cm (2.17 in) from the neutralizer plate. Thermocouples attached to the sample holder indicated a slight rise in temperature from 22 °C (72 °F) to approximately 50 °C (122 °F) where it remained over the test period. The increase in temperature was primarily due to heat radiating from the neutralizer plate and from the magnets. Kapton<sup>TM</sup> and Lexan<sup>TM</sup>, materials of known AO reactivity, indicated the AO fluence of test run No. 1 was  $1.2 \times 10^{21}$  atoms/cm<sup>2</sup> for the four samples located in the center of the holder and  $6.3 \times 10^{20}$  atoms/cm<sup>2</sup> for the samples located an AO fluence of  $1.1 \times 10^{21}$  atoms/cm<sup>2</sup> for the center samples and an AO fluence of  $5.6 \times 10^{20}$  atoms/cm<sup>2</sup> for the remaining samples. These samples also received approximately 8,000 ESH of VUV radiation.

Unlike the PPPL facility that is capable of producing neutral 5-eV AO, the AODTS facility (fig. 2) produces a thermal AO plasma. Generated by a 14.7-MHz RF field, the AODTS plasma contains both AO atoms and ions, molecular oxygen atoms and ions, and excited state atoms and electrons. However, the AODTS facility is designed such that samples are exposed outside the RF field. This eliminates sample exposure to any plasma charged particles and unwanted sample heating.

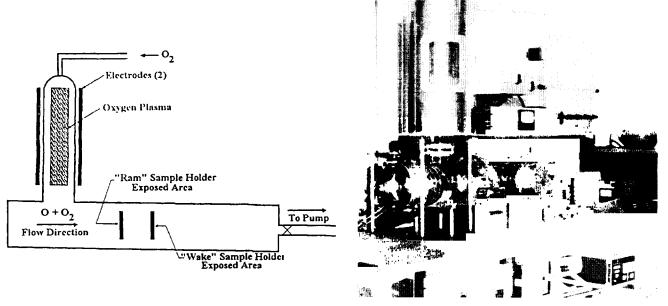


Figure 2. AODTS thermal AO test system.

A total of twenty-eight 2.54-cm (1-in) diameter samples were exposed in the AODTS system using the same two sample fixtures used in the PPPL test series. Fourteen samples were tested such that the exposed surface faced in the general drift direction ("ram"), while a second set of 14 samples faced 180° from the drift direction ("wake"). The AO plasma was generated using an RF power of 150 W. Samples were exposed at a test pressure of 90 mtorr and an average test temperature, as monitored by thermocouples attached to the sample holders, of 25 °C (77 °F). Polyethylene samples were used to monitor the total AO flux for both the ram and wake positions. Over the testing period, the AODTS chamber was brought up to atmospheric pressure a total of four times in order to remove and replace the polyethylene monitoring samples. Total sample exposure time was just over 64 days (1,538.11 hours), producing a ram AO fluence of  $7.1 \times 10^{22}$  atoms/cm<sup>2</sup> and a wake fluence of  $2.1 \times 10^{22}$  atoms/cm<sup>2</sup>.

#### **Black Duranodic Anodized Aluminum**

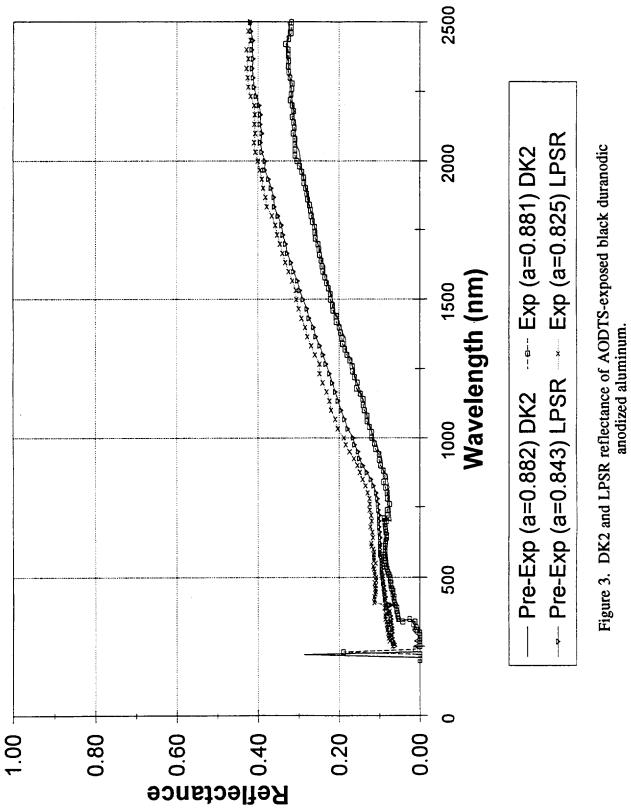
A total of six duranodic samples<sup>\*</sup> were tested, of which two were used as lab controls, two were exposed in the AODTS test, while the remaining two were exposed in the PPPL test. In the PPPL test, one sample was fully exposed to the environment, while the other was protected from AO by a UV-transmitting window. Sample coating thickness of 47.2  $\mu$ m (1.86 mils) was measured before exposure.

No visible change in appearance was noted following exposure in either the PPPL or AODTS facility. Mass, coating thickness, reflectance/solar absorptance, and infrared emittance measurements were made on all the samples both pre- and posttest. LPSR and DK2 reflectance curves for both the AODTS- and PPPL-exposed specimens are shown in figures 3 and 4, while mass, coating thickness, solar absorptance, and infrared emittance raw data are included in appendices A and B.Table 1 summarizes the optical data for both the PPPL- and AODTS-exposed duranodic samples. Infrared emittance for these and all other samples was measured with a Gier-Dunkle DB100 infrared reflectometer. The average preexposure values were derived from data taken on the two control and the two test samples for each respective test prior to exposure. By way of comparison, McDonnell Douglas Aerospace reported pretest values for the Duranodic samples at 0.87 for solar absorptance, using a Perkin-Elmer Lambda 9 reflectometer, and 0.87 for infrared emittance (corrected). Although the LPSR and the DK2 differ in the absolute value of solar absorptance, both do indicate that the solar absorptance was not greatly affected by exposure. The greatest change in solar absorptance was indicated by the LPSR, with an approximately 2.4-percent decrease as a result of the PPPL UV exposure. Emittance values were unchanged as a result of exposure in the PPPL test and AODTS test.

Exposure	Fluence		xposure     AODTS Exposision       10 <sup>20</sup> atoms/cm <sup>2</sup> AODTS Exposision       3,000 ESH (130 nm)     Fluence ~ 2.1×10 <sup>22</sup> atom				
	LPSR $\alpha_s$	DK2 $\alpha_s$	EIR	LPSR $\alpha_s$	DK2 $\alpha_s$	<i>E<sub>IR</sub></i>	
Average preexposure	0.84	0.88	0.88	0.84	0.89	0.88	
Posttest controls	0.84	0.88	0.88	0.84	0.88	0.88	
VUV-exposed	0.82	0.89	0.88				
5 eV AO+VUV	0.83	0.89	0.88				
Thermal AO				0.83	0.88	0.88	

Table 1. Black duranodic anodized aluminum test results.

<sup>\*</sup> Duranodic and sulfuric acid anodized aluminum samples provided by Cherie Jones, McDonnell Douglas Aerospace, Huntington Beach, CA.



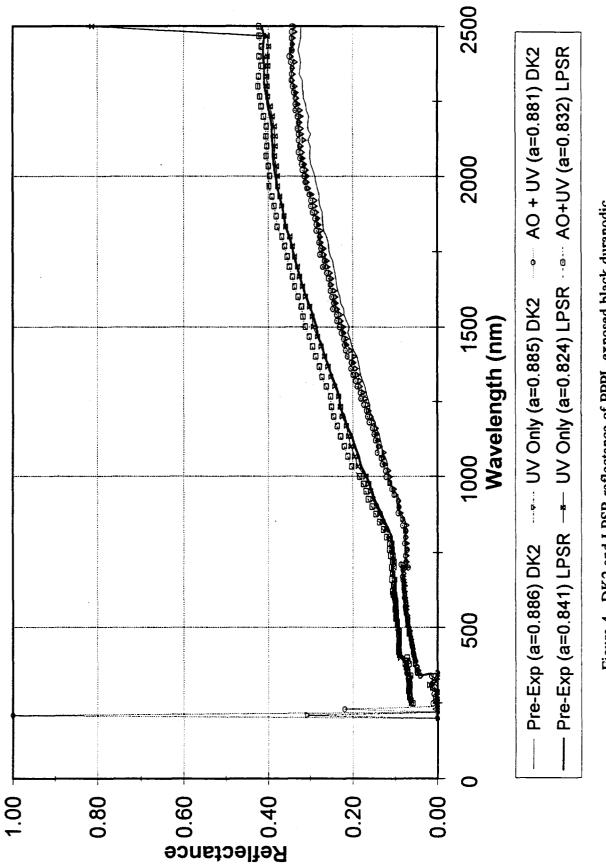


Figure 4. DK2 and LPSR reflectance of PPPL-exposed black duranodic anodized aluminum.

#### **Chromic Acid Anodized Aluminum**

A total of 15 chromic acid anodized (CAA) aluminum samples<sup>†</sup> were tested for susceptibility to AO and VUV degradation. Five samples each of three different anodized coating thickness, noted here in order of decreasing thickness as 75TK, 45MM, and 30TN, were evaluated. Two samples of each set were exposed in the AODTS test, two were exposed in the PPPL test, and the remaining sample used as a lab control. In the PPPL test, one sample was fully exposed to the environment while the other was protected from AO by a UV-transmitting window.

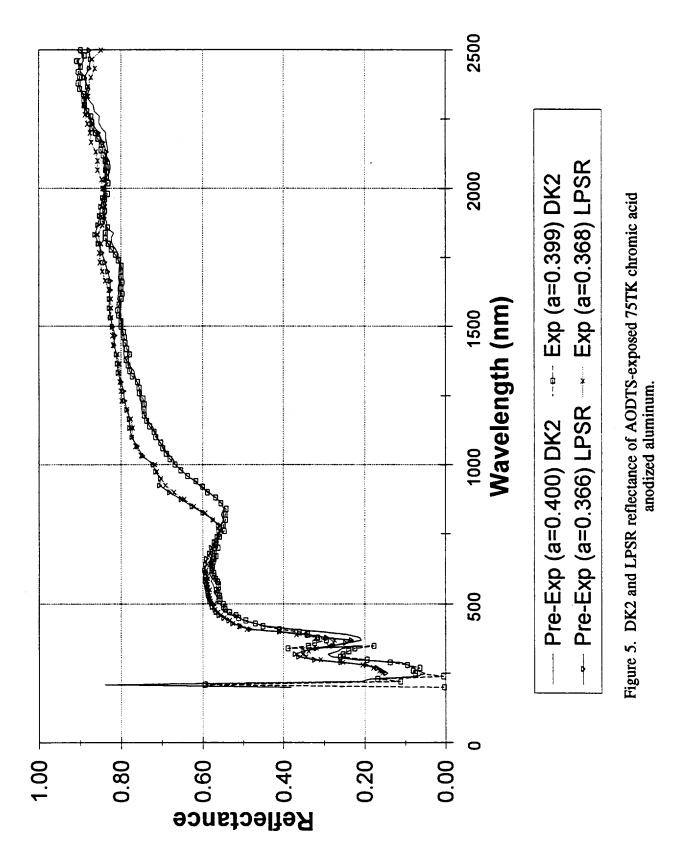
No visible change in appearance was noted following exposure in either the PPPL or AODTS facility. Mass, coating thickness, reflectance/solar absorptance, and infrared emittance measurements were made on all the CAA samples before and after exposure. LPSR and DK2 reflectance curves of the various anodize thicknesses are shown in figures 5 through 10, while mass, coating thickness, solar absorptance, and infrared emittance raw data are shown in appendices A and B.

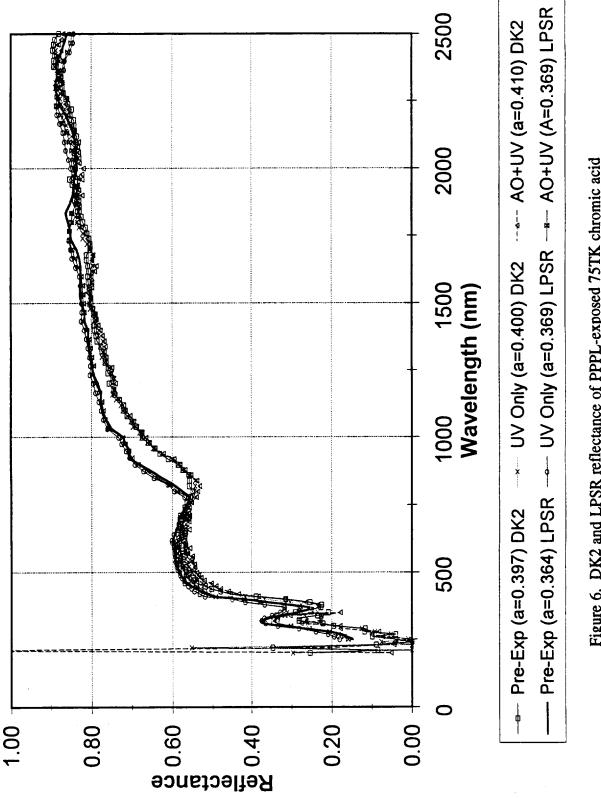
Table 2 summarizes the optical data for both the PPPL- and AODTS-exposed CAA samples. The average preexposure values were derived from data taken on the control and the two test samples for the AODTS test prior to exposure. Although the LPSR and the DK2 differ in the absolute value of solar absorptance, both do indicate that the solar absorptance was not greatly affected by exposure. Variations in the 30TN sample reflectance indicate an extremely thin oxide layer with some scatter from the substrate. Emittance values for the thicker 75TK samples were stable following exposure in the PPPL test and AODTS test. Emittance values for the thinner 45MM and 30TN samples showed a decrease ranging from 4 to 13 percent.

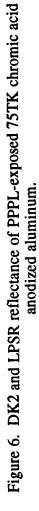
Type CAA	Exposure	PPPL Exposure Fluence ~ 6.8×10 <sup>20</sup> atoms/cm <sup>2</sup> VUV Irradiance ~ 8,000 ESH (130 nm)			AODTS Exposure Fluence ~ 2.1×10 <sup>22</sup> atoms/cm <sup>2</sup>		oms/cm <sup>2</sup>
		LPSR $\alpha_s$	DK2 $\alpha_s$	E <sub>IR</sub>	LPSR $\alpha_s$	DK2 $\alpha_s$	EIR
75TK	Average preexposure	0.36	0.40	0.73	0.37	0.40	0.73
75TK	Posttest controls				0.37	0.40	0.73
75TK	VUV exposed	0.37	0.40	0.73			
75TK	5 eV AO+VUV	0.37	0.41	0.73			
75TK	Thermal AO				0.37	0.40	0.72
45MM	Average preexposure	0.34	0.37	0.50	0.34	0.36	0.50
45MM	Posttest controls				0.33	0.36	0.50
45MM	VUV exposed	0.33	0.37	0.48			
45MM	5 eV AO+VUV	0.33	0.37	0.48			
45MM	Thermal AO				0.33	0.36	0.49
30TN	Average preexposure	0.29	0.32	0.30	0.29	0.32	0.30
30TN	Posttest controls				0.29	0.33	0.30
30TN	VUV exposed	0.29	0.32	0.28			
30TN	5 eV AO+VUV	0.28	0.32	0.26			
30TN	Thermal AO				0.29	0.32	0.29

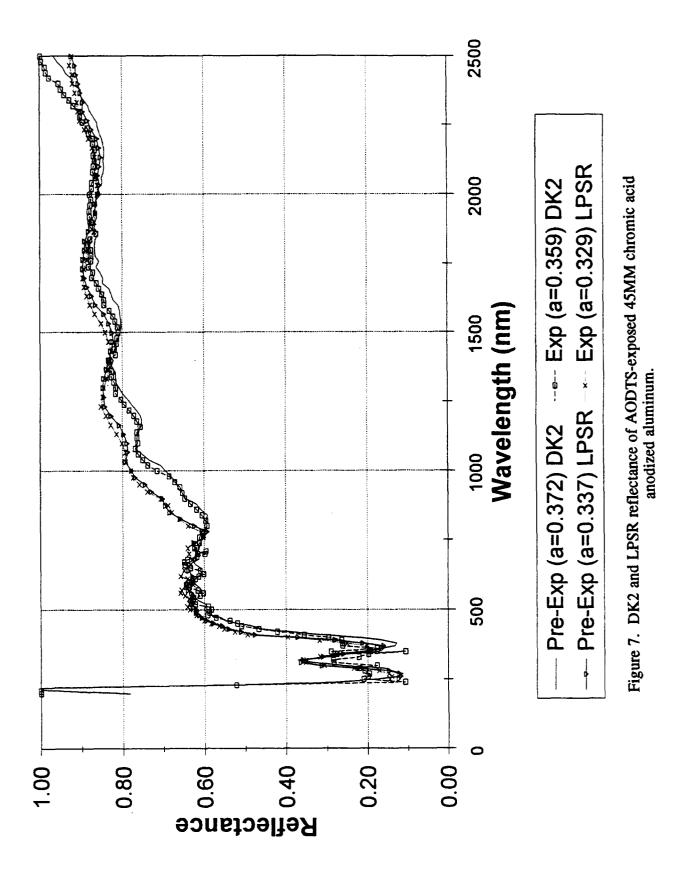
Table 2. CAA aluminum test resul
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<sup>&</sup>lt;sup>†</sup> Samples provided by Johnny Golden, Boeing Aerospace, Seattle, WA.









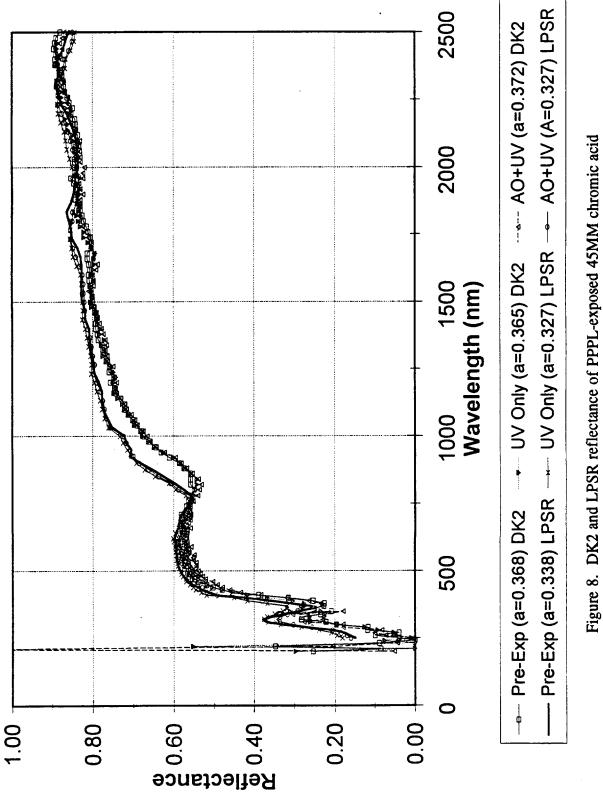
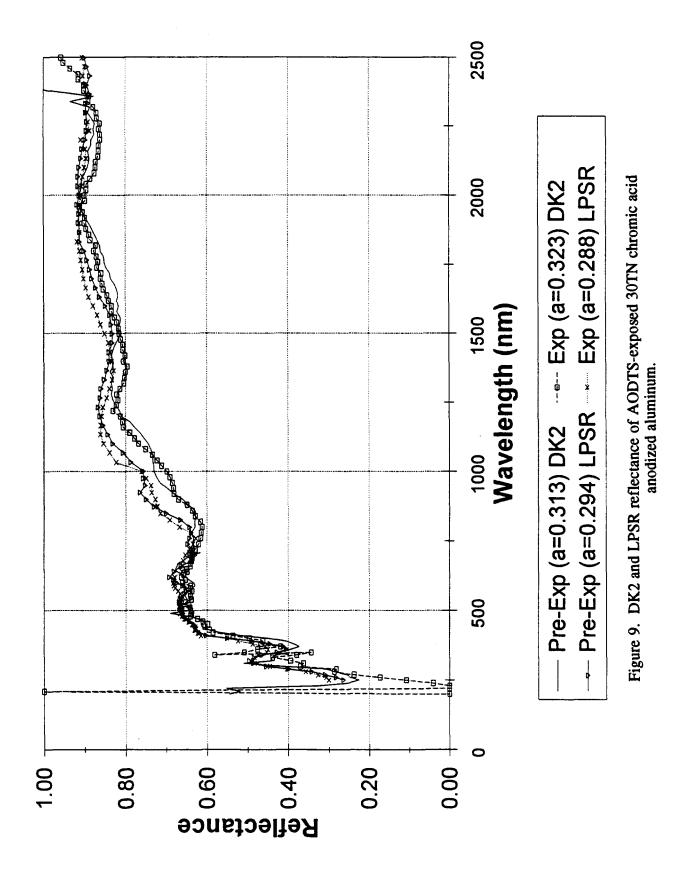
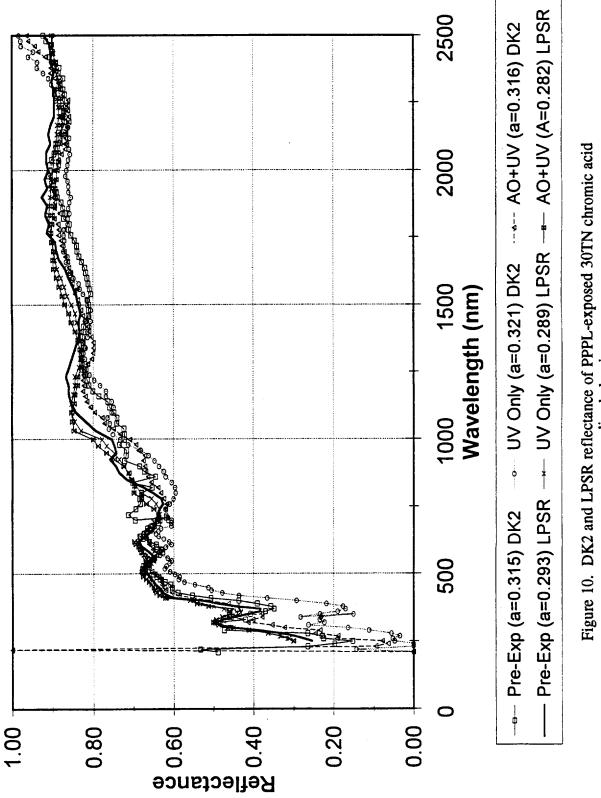


Figure 8. DK2 and LPSR reflectance of PPPL-exposed 45MM chromic acid anodized aluminum.





anodized aluminum.

#### Sulfuric Acid Anodized Aluminum

A total of six sulfuric acid anodized (SAA) aluminum samples were tested, of which two were used as lab controls. Two of the six were exposed in the AODTS test while the remaining two were exposed in the PPPL test. In the PPPL test, one sample was fully exposed to the environment, while the other was protected from AO by a UV-transmitting window. Pretest coating thickness was reported to be 15.2  $\mu$ m (0.6 mils).

No visible change in appearance was noted following exposure in either the PPPL or AODTS facility. Mass, coating thickness, reflectance/solar absorptance, and infrared emittance measurements were made on all the SAA samples before and after exposure. LPSR and DK2 reflectance curves are shown in figures 11 and 12, while mass, coating thickness, solar absorptance, and infrared emittance raw data are shown in appendices A and B.

Table 3 summarizes the optical data for both the PPPL- and AODTS-exposed SAA samples. The average preexposure values were derived from data taken on the two control and the two test samples for each respective test prior to exposure. By way of comparison, McDonnell Douglas reported pretest values of 0.45 for solar absorptance using a Perkin Elmer Lambda 9 spectroreflectometer and 0.86 for infrared emittance. Although the LPSR and the DK2 differ in the absolute value of solar absorptance, both do indicate that the solar absorptance was not greatly affected by exposure. Emittance values were also unchanged as a result of exposure in the PPPL test and AODTS test.

Exposure	Fluence	PL Exposure ~ 1.2×10 <sup>20</sup> atom nce ~ 8,000 ESF	ns/cm <sup>2</sup>		DTS Exposur ~ 7.1×10 <sup>22</sup> atom	
-	LPSR $\alpha_s$	DK2 $\alpha_s$	EIR	LPSR $\alpha_s$	DK2 $\alpha_s$	E <sub>IR</sub>
Average preexposure	0.40	0.45	0.86	0.40	0.45	0.86
Posttest controls				0.41	0.45	0.86
VUV exposed	0.40	0.45	0.86			
5 eV AO+VUV	0.41	0.46	0.86			
Thermal AO				0.39	0.44	0.86

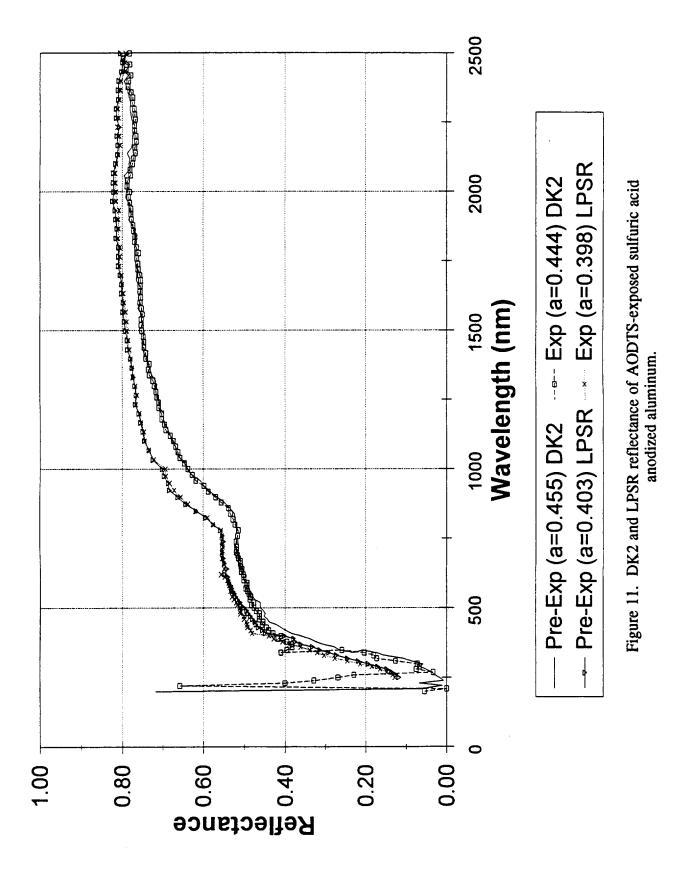
Table 3.	SAA	aluminum	test	results.
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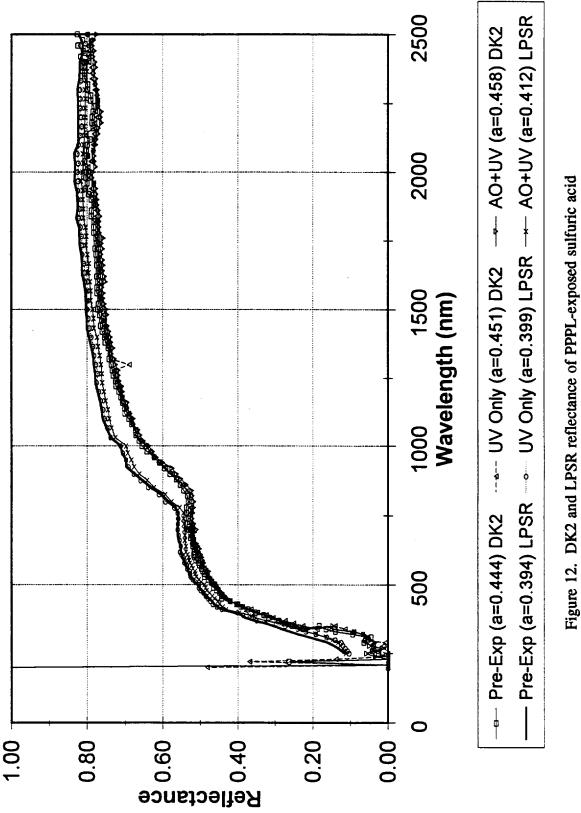
#### **Black Inorganic Paint**

A newly developed black inorganic paint<sup>‡</sup> composed of a copper oxide-iron oxide mixture with a potassium silicate Kasil 2130 binder was evaluated for AO sensitivity. A total of five paint samples were tested and evaluated, of which one was used as a lab control. Two of the five were exposed to thermal AO in the AODTS test, while the remaining two were exposed to 5-eV oxygen in the PPPL test.

No visible change in appearance was noted following exposure in either the PPPL or AODTS facility. Reflectance/solar absorptance and infrared emittance measurements were made on all the paint samples prior to and following exposure. LPSR and DK2 reflectance curves are shown in figures 13 and 14 while mass, coating thickness, solar absorptance and infrared emittance raw data are shown in appendices A and B.

<sup>&</sup>lt;sup>‡</sup> Samples provided by Richard Mell, AZ Technology, Huntsville, AL.





anodized aluminum.

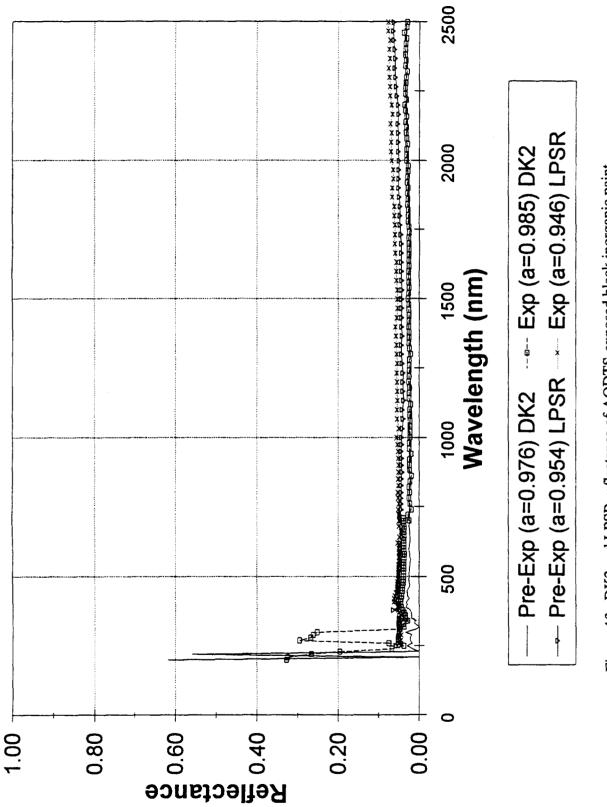


Figure 13. DK2 and LPSR reflectance of AODTS-exposed black inorganic paint.

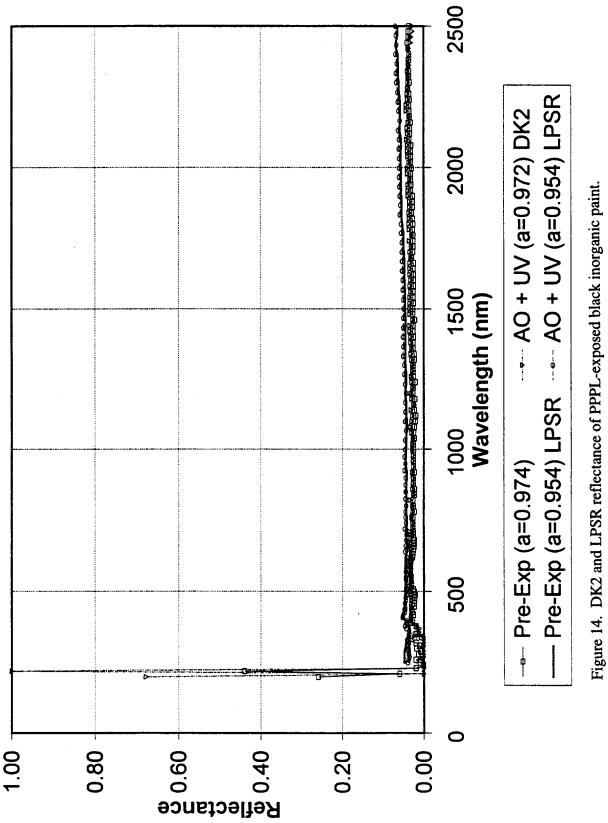


Table 4 summarizes the optical data for both the PPPL- and AODTS-exposed paint samples. The average preexposure values were derived from data taken using the control and the two test samples for the AODTS test prior to exposure. Although the LPSR and the DK2 differ in the absolute value of solar absorptance, both do indicate that the solar absorptance was not greatly affected by exposure. Emittance values were also unaffected by exposure in the PPPL test and AODTS test.

Exposure	Fluence	PPL Exposure ~ 7.2×10 <sup>20</sup> aton nce ~ 8,000 ESF	ns/cm <sup>2</sup>	AODTS Exposure Fluence ~ 2.1×10 <sup>22</sup> atoms/cm <sup>2</sup>			
	LPSR $\alpha_s$	DK2 $\alpha_s$	<i>E<sub>IR</sub></i>	LPSR $\alpha_s$	DK2 $\alpha_s$	€ <sub>IR</sub>	
Average preexposure	0.95	0.97	0.89	0.95	0.98	0.90	
Posttest controls				0.95	0.97	0.90	
VUV exposed	0.95	0.97	0.89				
Thermal AO				0.95	0.98	0.90	

Table 4. Black inorganic paint test results.

#### **Z93 White Paint**

A series of tests were conducted on the AO/AO+UV stability of the "new" Z93 coating made using K2130 binder as compared to the "original" Z93 made using the PS7 binder. Both PS7 and K2130 binder coatings were tested for AO stability in the AODTS system. The Illinois Institute of Technology Research Institute (IITRI) supplied a batch of PS7 and K2130 binder Z93 samples<sup>§</sup> for testing. In addition, McDonnell Douglas Aerospace supplied a batch of PS7 and K2130 binder Z93 samples<sup>\*\*</sup> for AODTS testing. No visible change in appearance was noted following exposure in the AODTS facility. Table 5 summarizes the thermal properties measured both pre- and posttest for the PS7 and K2130 binder samples exposed in the AODTS. The average preexposure values were derived from data taken on the controls and the two test samples for each respective test prior to exposure. DK2 reflectance for exposed IITRI samples with PS7 and K2130 is shown in figure 15 (no LPSR data available). DK2 reflectance for some

AO Fluence ~ $2.1 \times 10^{22}$ atoms/cm <sup>2</sup>	Original PS7 Binder		New Kasil 2130 Binder						
	LPSR $\alpha_s$	DK2 $\alpha_s$	E <sub>IR</sub>	LPSR $\alpha_s$	DK2 $\alpha_s$	£ <sub>IR</sub>			
IITRI Z93									
Average preexposure		0.16	0.92		0.16	0.92			
Posttest controls		0.15	0.92		0.16	0.92			
Thermal AO exposed	0.15	0.16	0.92	0.15	0.16	0.92			
	]	McDonnell D	ouglas Z93						
Average preexposure	0.14	0.17	0.92	0.15	0.17	0.93			
Posttest controls	0.15	0.16	0.92	0.16	0.17	0.92			
Thermal AO exposed	0.15	0.16	0.91	0.16	0.17	0.92			

Table 5. Z93 AODTS test results.

<sup>§</sup> Samples provided by Dr. Yosh Harada, IITRI, Chicago, IL.

<sup>\*\*</sup> Samples provided by Hank Babel, McDonnell Douglas, Huntington Beach, CA.

of the IITRI-supplied PS7- and K2130-exposed samples is shown in figure 15 (no LPSR data available). LPSR and DK2 reflectance curves for the McDonnell Douglas PS7 and K2130 samples can be found in figures 16 and 17. Solar absorptance and infrared emittance raw data for all the samples can be found in appendices A and B. As evident from the data, both solar absorptance and infrared emittance were not significantly affected by the test exposures. Water desorption was noted, as shown in the slight increase in infrared reflectance.

Two samples of each binder formulation supplied by IITRI were also tested at the PPPL facility, configured such that one of each binder type was protected from AO by a UV-transmitting window. The K2130 binder samples initially appeared dry and cracked; exposure in the PPPL test caused the paint to flake away from the aluminum substrate and thus no posttest data could be taken. Table 6 summarizes the optical properties measured pre- and posttest for the PS7 binder samples exposed in the PPPL test. LPSR and DK2 reflectance curves for the Z93 PS7 samples can be found in figure 18. As in the AODTS test, both solar absorptance and infrared emittance were not significantly affected by the AO exposure.

	PPPL Exposure			
	Fluence ~ $7.2 \times 10^{20}$ atoms/cm <sup>2</sup>			
IITRI Z93/PS7 Binder	VUV Irradiance ~ 8,000 ESH (130 nm)			
Exposure	LPSR $\alpha_s$	DK2 $\alpha_s$	E <sub>IR</sub>	
Average preexposure	0.15	0.17	0.92	
VUV exposed	0.15	0.16	0.92	
5 eV AO+VUV	0.15	0.16	0.92	

T	able	6.	Z93	PPPL	test	results.
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#### Polymers

Bulk samples of Halar<sup>TM</sup>, a copolymer of chlorotrifluoroethylene and ethylene, PEEK, and 1-in button samples of 127- $\mu$ m (0.005-in) silverized FEP Teflon<sup>TM</sup> tape were exposed in the PPPL and AODTS test systems. In the PPPL test a UV-transmitting window was used to protect one of the two silver Teflon<sup>TM</sup> test samples from AO, thus exposing the sample to VUV radiation only. Both the Halar<sup>TM</sup> and PEEK samples appeared lighter in the exposed region as a result of exposure in the PPPL and AODTS test systems. The silverized Teflon<sup>TM</sup> specimen exposed to both AO and VUV radiation in the PPPL test appeared more diffuse and white in color in the exposed region, but the specimen that was exposed to only VUV showed no visible change in appearance. The AODTS-exposed silverized Teflon<sup>TM</sup> appeared to have a slight milky white film over the exposed region. Mass, thickness change, and some optical data can be found in appendices A and B. Reflectance curves for the AgFEP samples can be found in figures 19 and 20. Solar absorptance and infrared emittance values for the AgFEP samples are summarized in table 7. AO reaction efficiencies for all three polymers were calculated based on mass and thickness change. These values can be found in table 8 along with previous shuttle flight data for comparison.

#### **Beta** Cloth

One sample each of Chemfab 250 beta cloth and aluminized beta cloth was exposed to VUV radiation only in the PPPL test. Samples were protected from AO by a UV-transmitting window. Posttest visual observations indicated that both beta cloth samples appeared slightly yellow in the exposed region. In addition, one sample of aluminized beta cloth, previously exposed to approximately 700 ESH of enhanced ultraviolet (EUV) radiation from 250 to 400 nm in the EH15 EUV solar simulator, was exposed

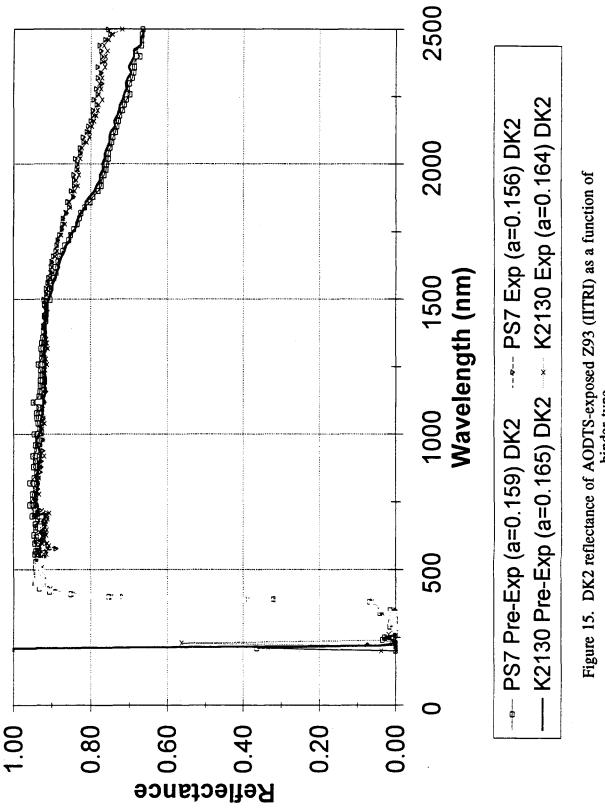
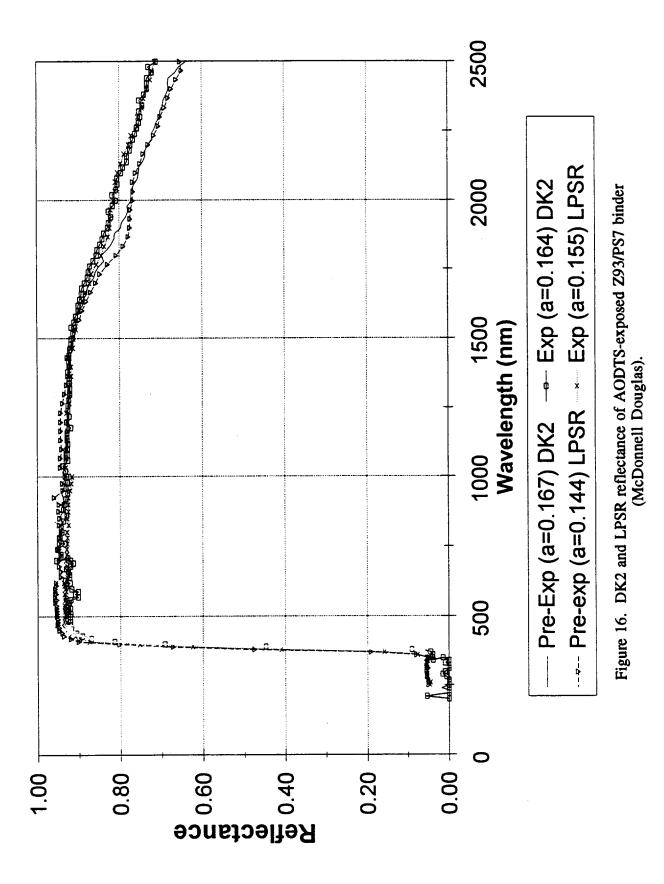
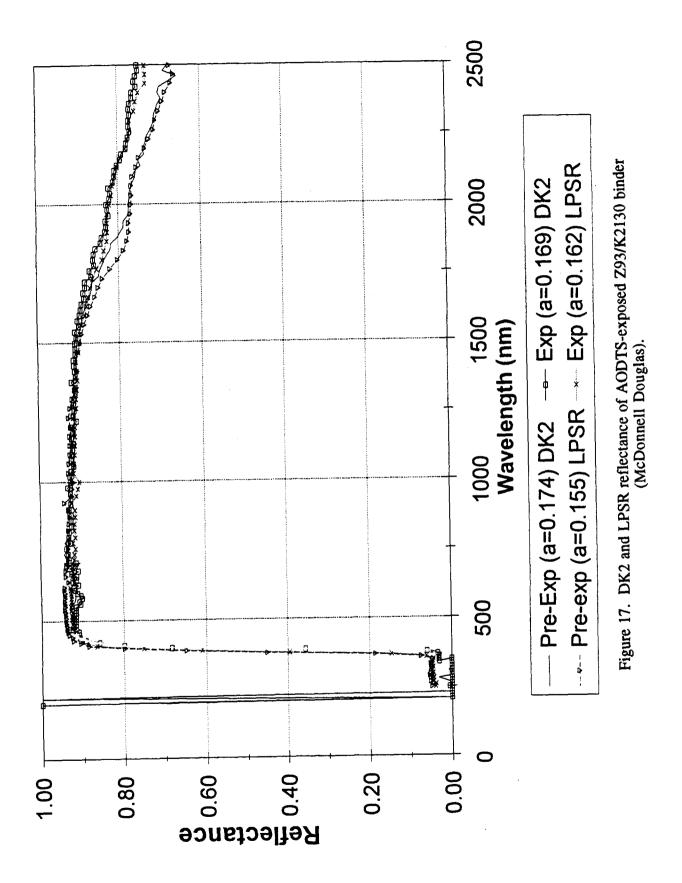


Figure 15. DK2 reflectance of AODTS-exposed Z93 (IITRI) as a function of binder type.





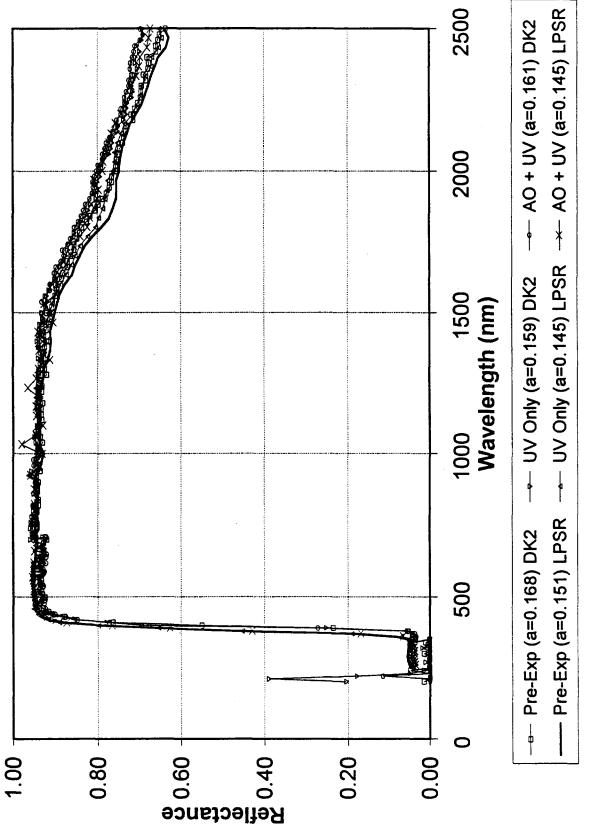


Figure 18. DK2 and LPSR reflectance of PPPL-exposed Z93/PS7 binder (IITRI).

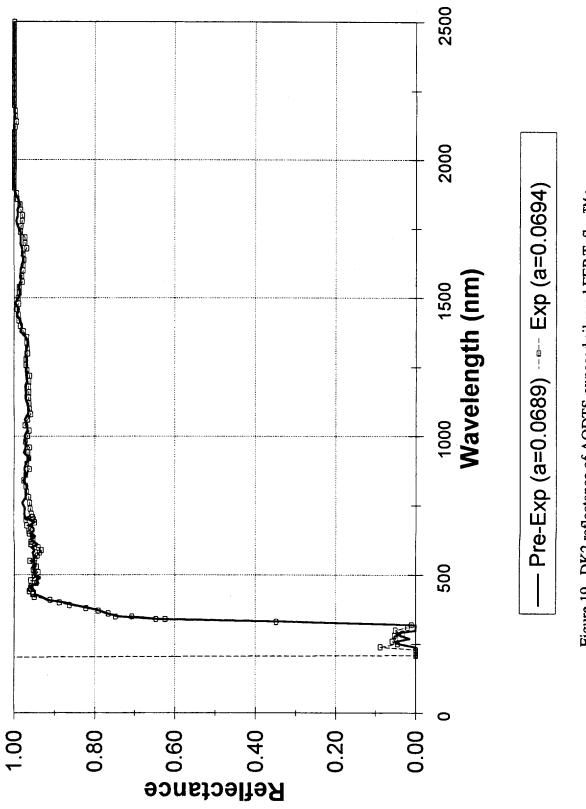


Figure 19. DK2 reflectance of AODTS-exposed silvered FEP Teflon<sup>TM</sup> tape.

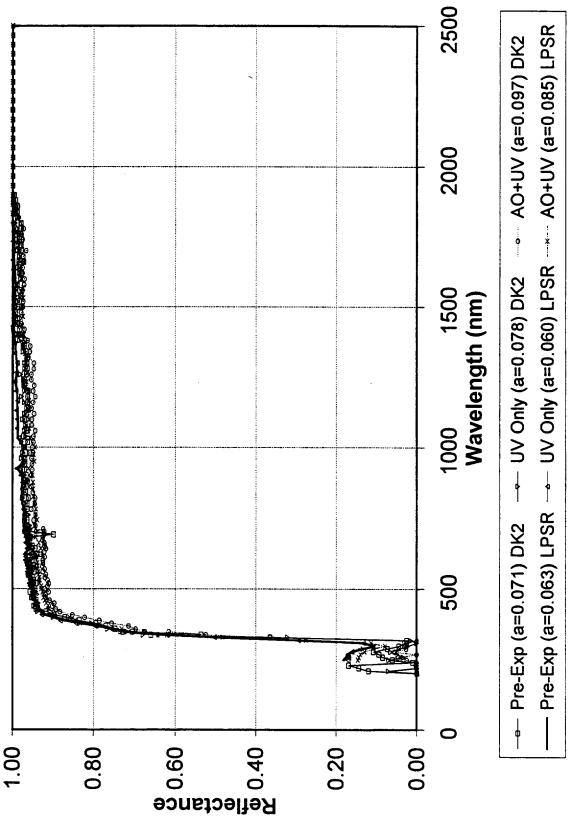


Figure 20. DK2 and LPSR reflectance of PPPL-exposed silverized FEP Teflon<sup>TM</sup> tape.

Exposure	Fluence	PPL Exposure ~ 1.1×10 <sup>20</sup> atom nce ~ 8,000 ESH	ns/cm <sup>2</sup>		DTS Exposur ~ $7.1 \times 10^{22}$ atom	
	LPSR $\alpha_s$	DK2 $\alpha_s$	E <sub>IR</sub>	LPSR $\alpha_s$	DK2 $\alpha_s$	€ <sub>IR</sub>
Average preexposure	0.062	0.072	0.80		0.069	0.81
VUV exposed	0.060	0.068	0.80			
5 eV AO+VUV	0.085	0.094	0.70			
Thermal AO				0.068	0.068	0.78

Table 7. Silverized Teflon<sup>™</sup> test results.

Table 8. Reaction efficiencies ( $\times 10^{-24}$  cm<sup>3</sup>/atom) for space- and lab-exposed polymers.

		A	O Reaction Ef	fficiency $\times 10^{-24}$ cm <sup>3</sup> /ato	om		
Sample	STS-5 and STS-8	MSFC STS-41	LDEF A0171	MSFC EOIM-3	JSC EOIM-3	PPPL	AODTS
Fluence atoms/cm <sup>2</sup>	1.0×10 <sup>20</sup>	1.0×10 <sup>20</sup>	6.93×10 <sup>21</sup>	2.2×10 <sup>20</sup>	2.2×10 <sup>20</sup>	7.2×10 <sup>20</sup> + 8,000 ESH VUV	7.10×10 <sup>22</sup>
Halar (bulk)		1.6 <sup>††</sup> 1.0 <sup>††</sup> 2.0 <sup>§§</sup>	2.1 <sup>§§</sup>	2.0 <sup>§§</sup> 2.5 <sup>††</sup>	2.1 <sup>§§</sup>	3.2 <sup>§§</sup> 3.4 <sup>§§</sup> 3.2 <sup>††</sup> 3.0 <sup>††</sup>	0.034 <sup>§§</sup> 0.023 <sup>§§</sup> 0.014 <sup>††</sup>
PEEK (bulk)		4.8 <sup>§§</sup>	2.3§§	2.0 <sup>§§</sup> 2.0 <sup>§§</sup> 3.7 <sup>††</sup> 4.0 <sup>††</sup>	3.9 <sup>§§</sup> Mfg. by Victrix	2.8 <sup>§§</sup> 3.0 <sup>††</sup>	0.11 <sup>§§</sup> 0.12 <sup>§§</sup>
FEP Teflon™ (film)	<0.05		0.34 <sup>††</sup> <a0178></a0178>	0.082† @ 60 °C 0.094† @ 120 °C 0.082† @ 120 °C	0.046	6.6 <sup>§§</sup> 5.9 <sup>††</sup> <agfep></agfep>	0.023 <sup>§§</sup> 0.023 <sup>††</sup> <agfep></agfep>

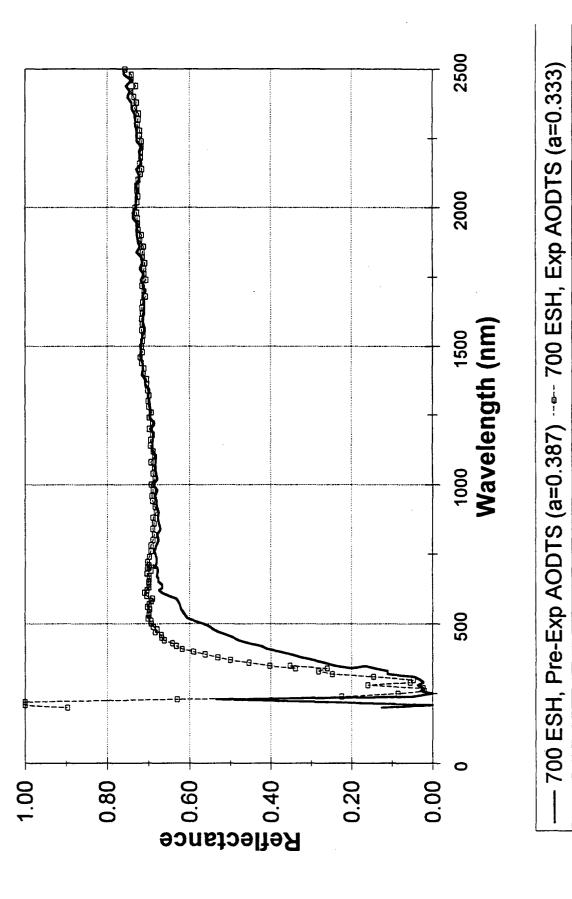
Atomic Reaction Efficiency

<sup>††</sup>Based on change in thickness

§§Based on change in mass

to thermal AO in the AODTS test. Examination of this sample prior to exposure in the AODTS test indicated that it had been clearly yellowed by the 700 ESH of EUV. Following AODTS exposure, the sample appeared in almost pristine condition, having been "cleaned" or bleached by the AO exposure. The decrease in solar absorptance following exposure in the AODTS system clearly verifies this cleaning effect. Mass, solar absorptance, and infrared emittance raw data for the samples are shown in appendices A and B. LPSR and DK2 reflectance curves are shown in figures 21, 22, and 23. Tables 9 and 10 summarize the optical data for the PPPL and AODTS tests.

Figure 21. DK2 reflectance of EUV irradiated aluminized beta cloth bleached by AODTS AO.



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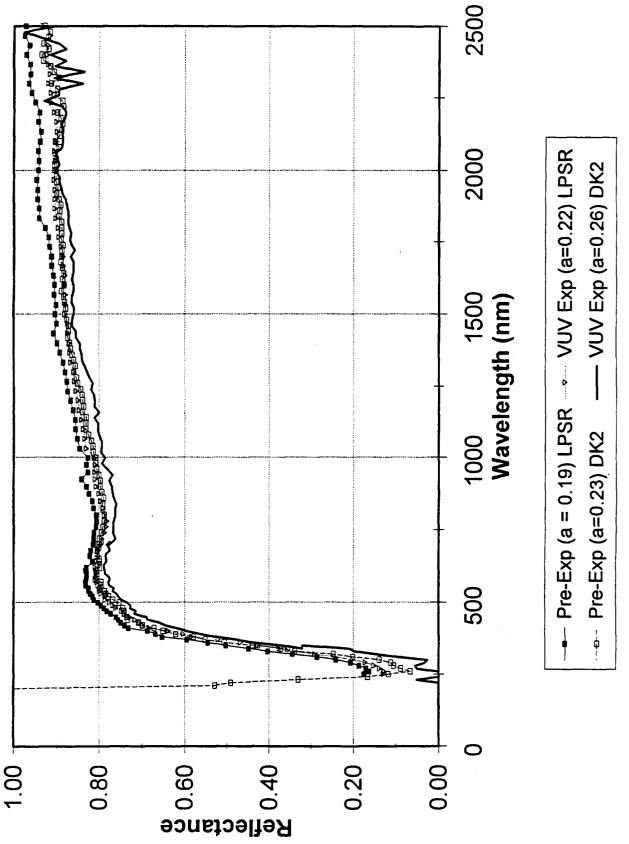


Figure 22. DK2 and LPSR reflectance of PPPL VUV-irradiated beta cloth.

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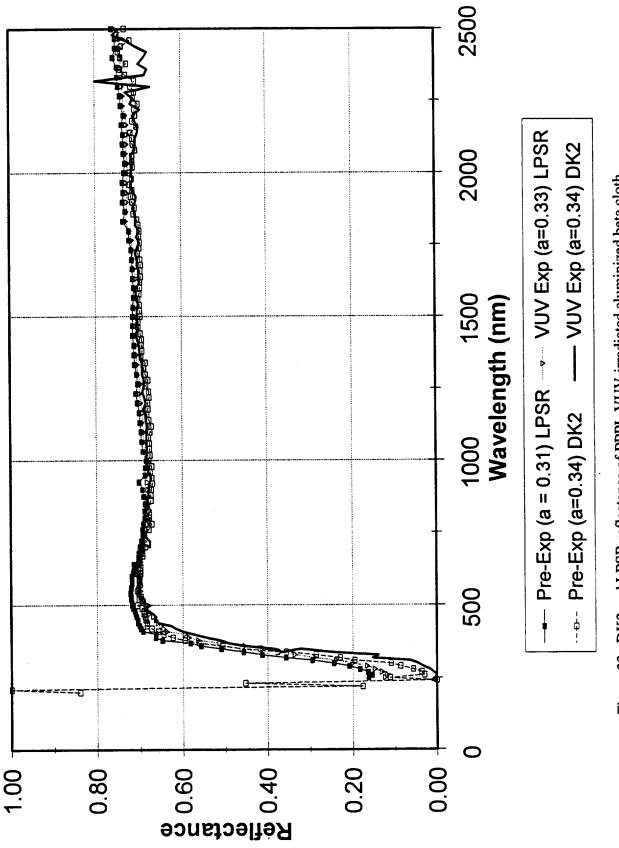


Figure 23. DK2 and LPSR reflectance of PPPL VUV-irradiated aluminized beta cloth.

Exposure		PL Exposure nce ~ 8,000 ESH	
_	LPSR $\alpha_s$	DK2 $\alpha_s$	E <sub>IR</sub>
Control – unaluminized	0.19	0.23	0.90
VUV exposed unaluminized	0.22	0.26	0.90
Control – aluminized	0.31	0.34	0.91
VUV exposed aluminized	0.33	0.34	0.90

Table 9. Test results of beta cloth exposed to PPPL VUV.

Table 10. Test results of aluminized beta cloth exposed to AODTS and EUV.

Exposure	2.1×10 <sup>20</sup> ato	PPL Exposure oms/cm <sup>2</sup> , EUV I ESH (250 to 400	rradiance
	LPSR $\alpha_s$	DK2 $\alpha_s$	E <sub>IR</sub>
Average preexposure	0.37	0.39	0.90
Thermal AO exposed	0.31	0.33	0.90

## CONCLUSIONS

In general, thermal properties of the black anodized, sulfuric anodized, and chromic anodized samples remained fairly stable following exposure in the PPPL and AODTS tests. In addition, both the black inorganic and the Z93 thermal control paints showed little to no variation in thermal properties following exposure in either test. Reaction efficiencies for the bulk Halar<sup>™</sup> and PEEK polymers exposed to AO and VUV in the PPPL test differ slightly from values generated from shuttle flight data. This slight difference is probably due to the VUV exposure in the PPPL test and slight differences in the chemical makeup of the different polymer sample lots. Bulk Halar<sup>™</sup> samples exposed to thermal AO in the AODTS system appeared to have reaction efficiencies on the order of 100 times less than those samples exposed to neutral 5-eV AO. Bulk PEEK samples exposed to thermal AO in the AODTS system appeared to have reaction efficiencies on the order of only 20 times less than those samples exposed to neutral 5-eV AO. Thermal properties of the silverized FEP samples remained fairly stable following exposure to VUV radiation only in the PPPL test and to thermal AO only in the AODTS test. However, silverized FEP samples showed a large variation in both reaction efficiency and thermal properties when exposed to synergistic 5-eV AO and VUV in the PPPL test. Beta cloth specimens showed a slight increase in solar absorptance due to VUV exposure in the PPPL system. Beta cloth samples previously darkened by EUV radiation experienced a "cleaning" effect when exposed to thermal AO in the AODTS system as indicated by both visual observations and solar absorptance measurements.

Both the LPSR spectroreflectometer and the DK2 spectroreflectometer were fairly consistent in reporting changes in solar absorptance due to test exposures. However, variation in solar absorptance was evident for most all specimens when comparing absolute values measured using the LPSR spectroreflectometer and those values measured using the DK2 spectroreflectometer. Beta cloth and chromic acid anodized samples appeared to show the greatest difference between LPSR and DK2 values, while the duranodic, black inorganic, and Z93 specimens appeared to be more consistent. As a result, care should be taken when quoting and requiring specific absolute values of solar absorptance.

## REFERENCE

1. Cuthbertson, J.W., Langer, W.D., Motley, R.W, and Vaughn, J.A.: "Atomic Oxygen Beam Source for Erosion Simulation." Fourth Annual Workshop on Space Operations Applications and Research, Albuquerque, NM, June 1990, NASA publication CP-3103, vol. II, pp. 734–741.

## APPENDIX A

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**AODTS Test Raw Data** 

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Exposure     Pre-test       Exposure     Pre-test       RAM     2.26776       Wake     2.27243       Wake     2.27243       Wake     2.15300       Wake     2.15300       RAM     1.61593       Wake     2.15300       Control     1.61593       RAM     1.61593       RAM     1.61593       RAM     1.61593       RAM     1.61593       RAM     1.61593       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43161       Ram     4.50379       Ram     4.50379       Ram     2.14335       RAM     2.14335       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376	Mass															
Exposure   Pre-test     (g)   (g)     RAM   2.26776     Wake   2.27343     RAM   1.61593     Wake   2.15300     Wake   2.15300     RAM   1.61593     RAM   1.61593     RAM   1.61593     RAM   1.61593     RAM   1.85592     Control   1.7650     Control   1.43003     Ram   1.43003     Control   1.43003     Ram   1.43003     Control   1.43003     Control   1.43003     Ram   1.43003     Control   1.43003     Control   1.43003     Ram   4.50379     Ram   4.50379     Ram   2.14330     RAM   2.14335     RAM   2.14335     RAM   2.14335     RAM   2.14335     RAM   2.14335     RAM   2.14335     RAM   2.14337     RAM   2.14335				Coating	Coating Thickness (Mils)	(Mils)		Ŭ	α, LPSR			α, DK2	<u></u>	Gier	Gier-Dunkle	εı,
RAM     2.26776       Wake     2.27243       Wake     2.27243       RAM     1.61593       Wake     2.15300       Wake     2.15300       RAM     1.61593       Wake     2.15300       RAM     1.85592       Control     1.7650       Control     1.43003       Ram     1.43003       Ram     1.43003       Control     1.43000       Control     1.43000       Control     1.43000       Ram     1.43000       Control     1.43000       Control     1.43000       Ram     4.50379       Ram     2.14303       Ram     2.14335       RAM     2.14735       RAM     2.14735       RAM     2.14735       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.14337 <th>Post-test (g)</th> <th>ΔM (mg)</th> <th>Pre-test</th> <th>Post-test</th> <th>ΔT (%)</th> <th>Pre-test</th> <th>Post-test σ/n</th> <th>Pre-test</th> <th>Post-test</th> <th>γα (%)</th> <th>Pre-test</th> <th>Post-test</th> <th>Δ (%)</th> <th>Pre-test Post-test</th> <th>Post-test</th> <th>Δ ε<sub>ι</sub>, (%)</th>	Post-test (g)	ΔM (mg)	Pre-test	Post-test	ΔT (%)	Pre-test	Post-test σ/n	Pre-test	Post-test	γα (%)	Pre-test	Post-test	Δ (%)	Pre-test Post-test	Post-test	Δ ε <sub>ι</sub> , (%)
RAM     2.26776       Wake     2.27243       Wake     2.27243       RAM     1.61593       Wake     2.15300       Wake     2.15300       Wake     2.15300       Wake     2.15300       Control     1.7650       Control     1.7650       Control     1.7650       Control     1.7650       Ram     1.43023       Ram     1.43023       Ram     1.43023       Ram     1.43023       Ram     1.43023       Ram     1.43023       Ram     2.14302       Control     1.43161       Control     1.43161       Ram     4.50377       Ram     4.50379       Ram     2.14330       Control     2.14335       RAM     2.14735       RAM     2.13376       RAM     2.13376       RAM     2.14337       RAM     2.14337       RAM     2.14337																
Wake     2.27243       RAM     1.61593       RAM     1.61593       Wake     2.15300       Wake     2.15300       Control     1.61593       RAM     1.61593       Ram     1.61500       Control     1.7650       Control     1.7650       Ram     1.43023       Ram     1.43000       Control     1.43000       Control     1.43000       Ram     1.43000       Control     1.43161       Ram     4.50837       Ram     4.50379       Ram     4.50379       Ram     4.4776       Control     1.43161       Ram     4.50379       Ram     2.14335       RAM     2.14335       RAM     2.14335       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.14337       RAM     2.14337       RAM     2.14337	2.26168	0.608			0.38°											
RAM     1.61593       Wake     2.15300       Wake     2.15300       RAM     1.85592       Control     1.7650       Control     1.7550       Control     1.7550       Control     1.43023       Ram     1.43023       Ram     1.43023       Ram     1.43000       Control     1.43000       Control     1.43000       Ram     1.43023       Ram     1.43023       Ram     4.50379       Control     1.43161       Control     1.43161       Ram     4.50379       Ram     4.50379       Ram     2.143300       Control     2.14330       RAM     2.14333       Control     2.14333       RAM     2.14333       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.14337       RAM     2.14337       RAM     2.14337	2.27124	0.119			•											
RAM     1.61593       Wake     2.15300       Wake     2.15300       RAM     1.85592       Control     1.7650       Control     1.7650       Control     1.7650       Control     1.43023       Ram     1.43008       Control     1.43008       Control     1.43000       Control     1.43000       Ram     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Ram     4.50379       Ram     4.50379       Ram     2.14308       Control     1.43161       Ram     2.14337       RAM     2.14335       RAM     2.14335       RAM     2.14335       RAM     2.14335       RAM     2.14335       RAM     2.13376       RAM     2.13376       RAM     2.14335       RAM     2.14337       RAM     2.14337 </td <td></td>																
Wake     2.15300       RAM     1.85592       Ram     1.7650       Control     1.7650       Control     1.7650       Control     1.43023       Ram     1.43003       Ram     1.43000       Control     1.43000       Control     1.43000       Ram     1.43000       Control     1.43000       Ram     1.43000       Control     1.43000       Ram     4.50379       Ram     4.50379       Ram     2.14300       Ram     2.14735       Ram     2.14735       Ram     2.14735       RAM     2.14735       RAM     2.14735       RAM     2.13376	1.60087	15.06			•				0.702				-		0.886	
RAM     I.85592       Control     1.7650       Control     1.7650       Control     1.7650       Control     1.7650       Ram     1.43008       Ram     1.43008       Control     1.43000       Control     1.43000       Control     1.43161       Control     1.43161       Ram     4.50377       Ram     4.50377       Ram     4.50377       Ram     2.143161       Control     2.14735       RAM     2.14735       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357 <tr td="">     2.14357</tr>	2.14790	5.10			•				0.764						0.889	
RAM     1.85592       Control     1.7650       Control     1.7650       Control     1.43023       Ram     1.43008       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43161       Control     1.43161       Ram     4.50837       Ram     4.50379       Control     1.43161       Ram     4.50379       Ram     2.1436       RAM     2.14336       RAM     2.14336       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.14337       RAM     2.14337       Control     2.14337       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357 <td></td>																
Control     1.7650       Control     1.43023       Ram     1.43023       Ram     1.43020       Control     1.43000       Control     1.43161       Control     1.43161       Control     1.43161       Ram     4.50379       Ram     4.50379       Control     4.4776       Control     4.49390       Ram     2.14337       RAM     2.14337       RAM     2.13376       RAM     2.14357	1.84225	13.67	6.43 Mil	5.79 Mil	0.640 Mil		0.126/10		0.068		0.06890	0.0694	0.73	0.808	0.784	-3.0
Control     1.43023       Ram     1.43023       Ram     1.43008       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43161       Ram     4.50837       Ram     4.50379       Control     4.4776       Control     4.4776       Control     2.14735       RAM     2.14735       RAM     2.13376       RAM     2.14337       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14235       Control     2.14127	-		6.48 Mil								0.06829			0.807		
Ram     1.43023       Ram     1.43008       Ram     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Ram     4.50379       Ram     4.50379       Control     4.4776       Control     4.4735       RAM     2.14735       RAM     2.14735       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357       Control     2.14357       Control     2.14127	2.4343			6.59 Mil			0.076/11		0.060			0.068				
Ram     1.43023       Ram     1.43000       Control     1.43000       Control     1.43000       Control     1.43000       Ram     4.50379       Ram     4.50379       Control     4.4776       Control     4.4776       Control     4.4735       Ram     2.14292       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14357       Control     2.14127       Control     2.14137																
Ram     1.42908       Control     1.43000       Control     1.43161       Control     1.43161       Ram     4.50379       Ram     4.50379       Control     4.4776       Control     4.49390       Control     4.49390       RAM     2.14292       RAM     2.14335       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14235       Control     2.14127	1.43069	0.460	1.4	1.4	0.0	0.015/10	0.006/10	0.843	0.825	-2.1	0.882	0.881	-0.11	0.882	0.880	-0.23
Control     1.43000       Control     1.43161       Ram     4.50837       Ram     4.50837       Ram     4.50837       Ram     4.50379       Control     4.4736       Control     4.49390       Control     2.14292       RAM     2.14292       RAM     2.14335       RAM     2.143376       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14127	1.42963	0.550	1.4	1.4	0.0	0.008/10	0.013/10	0.846	0.829	-2.0	0.888	0.887	-0.11	0.882	0.880	-0.23
Control     1.43161       Ram     4.50837       Ram     4.50379       Control     4.4776       Control     4.49390       RAM     2.14292       RAM     2.14293       RAM     2.143376       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14127	1.43056	0.560	1.4	1.4	0.0	0.016/10	01/600.0	0.837	0.835	-0.24	0.879	0.874	-0.57	0.883	0.880	-0.34
Ram     4.50379       Ram     4.50379       Ram     4.50379       Control     4.4776       Control     4.4736       RAM     2.14292       RAM     2.14333       Control     2.14735       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14235       Control     2.14127       Control     2.14127	1.43206	0.450	1.4	1.4	0.0	01//10.0	0.013/10	0.844	0.839	-0.59	0.893	0.881	-1.3	0.882	0.879	-0.34
Ram     4.50837       Ram     4.50379       Control     4.4776       Control     4.4736       Control     4.4736       RAM     2.14292       RAM     2.14735       RAM     2.14735       RAM     2.13376       RAM     2.14357       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       Control     2.14357       RAM     2.14357       RAM     2.14235       Control     2.14127																
Ram     4.50379       Control     4.4776       Control     4.49390       Control     4.49390       RAM     2.14292       RAM     2.14433       Control     2.14735       RAM     2.14735       RAM     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14357       RAM     2.14357	4.50879	0.420	0.56	0.56	0.000	0.034/20	0.036/15	0.403	0.398	-1.2	0.455	0.444	-2.4	0.858	0.861	0.35
Control     4.4776       Control     4.49390       RAM     2.14292       RAM     2.14333       Control     2.14433       RAM     2.14335       RAM     2.13376       Control     2.13376       RAM     2.13376       Control     2.13376       RAM     2.14357       RAM     2.14357       RAM     2.14127	4.50408	0.290	0.58	0.53	-0.050	0.028/20	0.038/10	0.395	0.390	-1.3	0.453	0.439	-3.1	0.856	0.859	0.35
Control     4.49390       RAM     2.14292       RAM     2.14333       RAM     2.14335       RAM     2.14335       RAM     2.13376       Control     2.13376       RAM     2.13376       RAM     2.13376       Control     2.13376       RAM     2.13376       Control     2.13376       RAM     2.14357       RAM     2.14357	4.47789	0.290	0.56	0.52	-0.040	0.026/20	0.020/10	0.394	0.396	0.51	0.449	0.440	-2.0	0.855	0.862	0.82
RAM     2.14292       RAM     2.14433       RAM     2.14435       RAM     2.14435       Control     2.1376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       Control     2.13376       RAM     2.13376       Control     2.13376       Control     2.13376       Control     2.14357       RAM     2.14355       Control     2.14127	4.49429	0.390	0.57	0.53	-0.040	0.022/20	0.022/10	0.406	0.414	2.0	0.455	0.459	0.88	0.858	0.864	0.70
RAM     2.14292       RAM     2.14735       Control     2.14735       RAM     2.13376       Control     2.14357       RAM     2.14357       RAM     2.14235       Control     2.14127															2 T	
RAM     2.14433       Control     2.14735       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       RAM     2.13376       Control     2.14357       RAM     2.14235       Control     2.14127	2.14276	-0.160	0.100	0.123	0.023 (23)	0.013/25	0.019/20	0.366	0.368	0.55	0.400	0.399	-0.25	0.731	0.724	-0.96
Control     2.14735       RAM     2.13376       RAM     2.13484       Control     2.13376       RAM     2.13484       Control     2.13376       RAM     2.13376       Control     2.13376       RAM     2.13376       Control     2.14357       RAM     2.14235       Control     2.14127	2.14405	-0.280	0.095	0.134	0.039 (41)	0.011/25	0.012/20	0.370	0.363	-1.9	0.397	0.398	0.25	0.731	0.725	-0.82
RAM     2.13376       RAM     2.13484       Control     2.13376       RAM     2.13375       RAM     2.14357       RAM     2.14235       Control     2.14127	2.14734	-0.0100	0.97	0.139	(98) [86]	0.010/25	0.011/20	0.364	0.366	0.55	0.399	0.396	-0.75	0.729	0.732	0.41
RAM     2.13484       Control     2.13376       RAM     2.14357       RAM     2.14235       Control     2.14127	2.13364	-0.120	0.080	0.073	0.007 (8.8)		0.014/20	0.337	0.329	-2.4	0.372	0.359	-3.5	0.506	0.490	-3.2
Control     2.13376       RAM     2.14357       RAM     2.14235       Control     2.14127	2.13475	-0.0900	0.080	0.091	0.011(13.8)	0.016/25	0.013/20	0.340	0.327	-3.8	0.366	0.366	0.0	0.501	0.488	-2.6
RAM     2.14357       RAM     2.14235       Control     2.14127	2.13319	-0.570	0.080	0.090	0.010(12.5)	0.011/25	0.008/20	0.337	0.325	-3.6	0.372	0.364	-2.2	0.506	0.496	-2.0
RAM 2.14235 Control 2.14127	2.14351	-0.0600	0.027	0.063	_	0.015/25	0.012/20	0.294	0.288	-2.0	0.313	0.323	3.2	0.306	0.295	-3.6
Control 2.14127	2.14231	-0.0400	0.021	0.066	0.045(214)	0.013/25	0.018/20	0.295	0.290	-1.7	0.323	0.321	-0.62	0.302	0.289	4.3
	2.14123	-0.0400	0.026	0.073		0.018/25	0.014/20	0.294	0.290	-1.4	0.331	0.328	16.0-	0.302	0.298	-1.3
Control 2.13653	2.13644	-0.0900	0.029	0.063	0.034 (117)	0.016/25	0.009/20	0.289	0.281	-2.8	0.319			0.294	0.287	-2.4
UV5+6	Beta 2					11. 12. 1										
ABC1b Wake 0.12933 0.	0.12920	-0.13	_					0.366	0.309	-15.6	0.387	0.333	-14.0	0.904	0.899	-0.55

April - June 1993

Ram Fluence = 7.1 x  $10^{21}$  atoms/cm<sup>2</sup> Wake Fluence = 2.1 x  $10^{22}$  atoms/cm<sup>2</sup>

			Mass			Coating	Coating Thickness (Mils)	(Mils)			o, LPSR			a, DK2		Gie	Gier-Dunkle	εľ
Sample	Exposure	Pre-test (g)	Post-test (g)	Δ M (mg)	Pre-test	Post-test	ΔT (%)	Pre-test σ/n	Post-test σ/n	Pre-test	Post-test	Δα (%)	Pre-test	Post-test	Δα, (%)	Pre-test Post-test		Δ ε <sub>ι</sub> , (%)
Iltri 293							Ì					Ì			Ì			
X31	Wake	1.83684									0.148		0.15885	0.156	-1.8	0.921	0.915	-0.65
X33	Control	1.85523									0.150		0.15284	0.154	0.76	0.921	0.918	-0.33
X40	Wake	1.82007	Stuck								0.152		0.15847			0.923	0.925	022
X27	Wakc	1.77525									0.156		0.16523	0.164	-0.74	0.921	0.915	-0.65
X28	Control	1.80166									0.153		0.15705	0.162	3.2	0.921	0.919	-0.22
X30	Wake	1.77579									0.152		0.16289	0.163	0.0	0.922	0.916	-0.65
Black Inorganic																		
3	Wake	2.01403			_					0.954	0.951	-0.31	0.977	0.974	-0.31	0.895	0.896	0.11
4	Wake	2.01612								0.954	0.946	-0.84	0.976	0.985	0.92	0.895	0.896	0.11
7	Control	2.00927								0.954	0.953	-0.10	0.980	0.966	-1.4	0.896	106'0	0.56
MacDac Z93																		
KS1 (new)	Wake	4.24926								0.155	.162	4.5	0.17361	0.169	-2.7	0.925	0.920	-0.54
KS2	Wake	4.21682								0.151	0.160	6.0	0.17226	0.168	-2.5	0.925	616.0	-0.65
KS3	Control	4.24743				•				0.153	0.159	3.9	0.17052	0.167	-2.1	0.925	0.923	-0.22
KS4	Control	4.35614								0.150	0.153	2.0	0.15950	0.164	3.1	0.926	0.924	-0.22
-	Mole Flux	4.22752								0.151			0.16594			0.926		
PSI (onig)	Wake	4.27462								0.144	0.155	7.6	0.16654	0.164	-1.5	0.917	0.912	-0.55
PS2	Wake	4.25676								0.140	0.154	10.0	0.16458	0.163	-0.96	0.917	0.913	-0.44
PS3	Control	4.29406					_			0.141	0.154	0.92	0.16593	0.160	-3.6	0.918	0.914	-0.44
PS4	Control	4.25968								0.147	0.148	0.68	0.16547	0.166	0.32	0.919	0.917	-0.22
PSS	Control	4.28809	-					-		0.145	0.153	5.5	0.16793	0.159	-5.3	616.0	0.915	-0.44

## APPENDIX B

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PPPL Test Raw Data

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	E <sub>lr</sub>	Δ ε <sub>ι</sub> ,	(%)		(11.0) 1	(6.23)						(51.0) 100.0	0.004 (0.47)					a jul	(11.0) 10			0.002 (0.22)			-0.006 (-0.82)	-0.007 (-0.95)	(13.6-) 610.0-	-0.025 (-5.0)	-0 021 (-7.0)	
		Post /			0.883 0.001	0.884 0.002						0.861 90	0.860 0.0						0.903 0.001	-		0.904			0.725 -00	0.726 -0.0	0.480 -0.0	0.478 -0.0	0.282 -00	
	Gier-Dunkle			37			82	82	83	82	9			58	56	55	58	05	0.0		02	5.0							<u> </u>	-
		Pre	Tei	0.87	0.882	3) 0.882	0.882	0.882	0.883	0.882	0.86	0.858	0.857	0.858	0.856	0.855	0.858	0.905			0.902				0.731	0.733	a) 0.499	0.503	0.303	-
		Δœ	(%)		(11.0-) 100.0-	-0.002(-0.23)						(9'1) 02:00'0	0.09 (0.0)						0.09 (2.7)			(6.61) (0.0			(91:0) (00:0	0.005 (1.2)	(23.0-) £00.0-	(ES-0-) too-o-	0.006 (1.9)	
	α, DK2	Post-test			0.885	0.881						0.451	0.458						0.344			0.256			0.400	0.410	0.365	0.372	0.321	
		Pre-test			0.886	0.879	0.882	0.888	0.879	0.893		0.444	0.449	0.455	0.453	0.449	0.455		0.335	0.331		0.226	0.242		0.397	0.405	0.368	0.374	0.315	
		Δα,	(%)		0.017 (-2.0)	0.0 (0.0)						(E'I) 500'0	(01) 1100						0.020 (6.4)			0.029 (15.0)			(1.1) 200.0	0.004 (1.1)	(6.6.) 110.0-	(6.6-) 110.0-	-0.004 (-1.4)	
	α, LPSR	Post-test			0.824	0.832						0.399	0.412						0.333		4	0.222			0.369	0.369	0.327	0.327	0.289	
		Pre-test		0.87	0.841	0.832	0.843	0.846	0.837	0.844	0.43* 0.45*	0.394	0.400	0.403	0.395	0.394	0.406		0.313	0.309		0.193	0.191		0.364	0.365	0.338	0.338	0.293	
eries 1	_	Post-test	α/n		0.013/20	0.012/20						0.035/20	0.030/20												0.012/25	0.012/25	0.009/25	0.013/25	0.012/25	
Test Series	(Mils)		¢∕n		0.014/13	01/800.0	0.015/10	01/800.0	0.016/10	01//10		0.027/20	0.034/20	0.034/20	0.028/20	0.026/20	0.022/20								0.009/25	0.011/25	0.008/25	0.011/25	0.011/27	
	Coating Thickness (Mils)	ΔT			0.00	0.00						0.000	0.000	-		_									0.040	0.040	0.000.0	0.100	0.030	
	Coating.	Post-test			1.4	1.4						0.56	0.58												0.14	0.14	0.080	0.070	0.050	
		Pre-test		1.86	1.4	1.4	1.4	1.4	1.4	4.1	0.60	0.56	0.58	0.56	0.58	0.56	0.57								0.10	0.10	0.080	080.0	0.020	
		ΔM	(mg)		0.08	0.07						0.07	0.11												-0.41	-0.27	-0.12	-0.14	-0.15	
	Mass	Post-test	(g)		1.43205	1.43177						4.56177	4.52907		i	-			0.12921			0.1343			2.14941	2.14482	2.13317	2.13442	2.14183	
		st	(g)		1.43197	1.43170	1.43023	1.42908	1.43000	1.43161		4.56170	4.52896	4.50837	4.50379	4.47746	4.49390		•						2.14982	2.14509	2.13329	2.13456	2.14198	
ļ		Exposure		None	PPPL-Win PR10	Iddd					None	PPPL-Win PR12	Tddd					None	PPPL-Win PR13		None	PPPL-Win PRI4			PPPL-Win PR15	JAPPL	PPPL-Win PR11	Iddd	PPPL-Win PR9	
	 	Sample F		Duranodic	ī	D2	D3	N.	DS	۲	Sulphuric	SI	S2	S3	S4	SS	S6	Al Beta Cloth'	ABC 1	ABC 2	Beta Cloth	BC 1	BC 2°	CAA	75TK1	75TK2	45MMI	45MM2	30TN1	

February - March 1993

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AO fluence  $\approx 6.84 \times 10^{20}$  atoms/cm<sup>2</sup> *Except* for S1 and S2 which had a fluence  $\approx 1.22 \times 10^{21}$  atoms/cm<sup>2</sup>

σ = Standard Deviation n = Number of measurements
Light Section Microscope
"Dek-Tak
"Eddy current

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February - March 1993 Test Series 2

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	┝╌┼	H		I MICKNESS				d LFSK			a UK2		Ö	Gier-Dunkle	e E <sub>lr</sub>
Δ M Pre-test	s-test		Pre-test	Post-test	Post-test $\sigma / n$	ΔT	Pre-test	Post-test	Δ α. (%)	Pre-test	Post-test	Δ α, (%)	Pre Test	Post Test	Δ ε,,
		100898													
							0.148			0.164			0.919		
-0.56							0.151	0.145	-0.006 (-4.0)	0.169	0.159	-0.010 (5.9)	0.920	0.919	(11.0-) 100.0-
-0.30							0.144	0.145	(69'0-) 100'0-	0.162	0.161	0.001 (0.62)	0.921	0.919	-0.002 (-0.22)
							0.137			0.160			0.919		
							0.136		   	0.160			0.919		
							0.143			0.167			0.919		
		100													
							0.954			0.977			0.895		
							0.954			0.976			0.896		
0.04							0.954	0.954	0.0 (0.0)	0.974	0.972	-0.002 (-0.21)	0.889	0.889	0.0 (0.0)
							0.951	0.955	0.004 (0.42)	0.970	0.973	(10.0) 000.0	0.895	0.892	(10.0-) 000.0-
							0.953			0.980			0.896		
-60.63 5.88" (Mill) 0.09		6	0.095/20	3.36 Mile)	0.056/20	2.52 (Mils)	0.0619	0.085	(5.75) 1620.0	0.0727	0.0942	0.0215 (30)	0.801	0.697	-0.104 (-13.0)
-1.07 5.13° (Mills)	(Mile)					•	0.0627	090.0	-0.0027 (-4.3)	0.0705	0.0675	-0.0030 (-1.2)	0.803	0.802	-0.001 (-0.12)
-6.08						22 µm"	0.763	0.776	0.013 (1.70)	0.516	0.525	(L'1) 600'0	0.921	0.934	(1.1) (1.0)
-6.55						22 µm"	0.766	0.773	(16:0-)L00:0 -	0.483	0.554	0.071 (14.7)	0.921	0.941	0.020 (2.2)
4.56						20 µm"	0.722	0.728		0.752	0.743	(2:1-) 600:0-	0.889	0.919	0.030 (3.4)
							0.72			0.753			0.889		
		1 - C - C - C - C - C - C - C - C - C -											0.884		
-32.39		ŧ													

AO Fluence =  $7.2 \times 10^{20}$  atoms/cm<sup>2</sup> except for Ag Teflon #1 and #2 which had a

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applications were eval the Princeton Plasma F MSFC Atomic Oxygen Dri anodized aluminum samp Teflon <sup>*</sup> -impregnated fi chromic acid anodize, glossy black paint and K2130 binder. Polymeri FEP Teflon <sup>*</sup> . Aluminize Samples were evaluated emittance. In addition reflectance/solar abso	uated for atomic oxyge Physics Laboratory 5 eV ft Tube System. Includ oles, ceramic paints, p berglass cloth. Alumin and sulfuric acid anod d Z-93 white paint made c samples evaluated in ed and nonaluminized Ch for changes in mass, to material effects,	n and vacuum ultravio Neutral Atomic Oxyge ed in this study were olymeric materials, a um anodizations teste ize. Paint samples co with the original PS cluded bulk Halar <sup>*</sup> , b emfab 250 <sup>*</sup> beta cloth thickness, solar abso an investigation was ade using a Beckman D	samples of various nd beta cloth, a d were black duranodic, nsisted of an inorganic 7 binder and the new ulk PEEK, and silverized were also exposed. rptance, and infrared made comparing diffuse K2 spectroreflectometer
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